

**AMENDMENTS TO THE SPECIFICATION**

Please amend the specification as follows:

Amend paragraph beginning on page 33, line 21 as follows:

(Example 1)

-Preparation of Resist Pattern Thickening Material-

Resist pattern thickening materials 1 through 4 of the present invention having the compositions shown in Table 1 were prepared. Note that, in Table 1, the unit of the values in parentheses is parts by mass. In the “resin” column, “KW-3” is a polyvinyl acetal resin (manufactured by Sekisui Chemical Co., Ltd.). In the “surfactant” column, “TN-80” is a non-ionic surfactant (a ~~polyoxyethylene monoalkylether~~ primary alcohol ethoxylate surfactant manufactured by Asahi Denka Co., Ltd.), and “PC-6” is a non-ionic surfactant (a ~~polyoxyethylene monoalkylether~~ special phenol ethoxylate surfactant manufactured by Asahi Denka Co, Ltd.). Further, a mixed liquid of pure water (deionized water) and isopropyl alcohol (whose mass ratio was water (deionized water): isopropyl alcohol = 98.6 : 0.4) was used as the main solvent component other than the resin.